

AMENDMENTS TO THE CLAIMS

- 1. (Original)** A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P.
- 2. (Currently Amended)** A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P and 0.01-2.0 mass% of at least one metallic element selected from In, Sn and Zn.
- 3. (Original)** A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P, 0.01-0.9 mass% of Au and/or 0.001-5.0 mass% of Pd and/or 0.01-0.9 mass% of Pt.
- 4. (Original)** A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P and 0.01-5.0 mass% of at least one metallic element selected from Cu, Ni, Fe and Bi.
- 5. (Original)** A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P, 0.01-2.0 mass% of at least one metallic element selected from In, Sn and Zn, 0.01 to 0.9 mass% of Au and/or 0.01-5.0 mass% of Pd and/or 0.01-0.9 mass% of Pt.
- 6. (Original)** A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P, 0.01-2.0 mass% of at least one metallic element selected from In, Sn and Zn, and 0.01-5.0 mass% of at least one metallic element selected from Cu, Ni, Fe and Bi.

7. (Original) A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P, 0.01-0.9 mass% of Au and/or 0.01-5.0 mass% of Pd and/or 0.01-0.9 mass% of Pt, and 0.01-5.0 mass% of at least one metallic element selected from Cu, Ni, and Bi.

8. (Original) A thin film-forming sputtering target material having high reflectance, characterized by being composed of an Ag base alloy containing 0.005-1.0 mass% of P, 0.01-2.0 mass% of at least one metallic element selected from In, Sn and Zn, 0.01-0.9 mass% of Au and/or 0.01-5.0 mass% of Pd and/or 0.01-0.9 mass% of Pt, and 0.01-5.0 mass% of at least one metallic element selected from Cu, Ni, Fe and Bi.

9. (Currently Amended) Thin film formed of an Ag base alloy as set forth in ~~any one of~~ Claims 1-8 Claim 1.

10. (New) Thin film formed of an Ag base alloy as set forth in Claim 2.

11. (New) Thin film formed of an Ag base alloy as set forth in Claim 3.

12. (New) Thin film formed of an Ag base alloy as set forth in Claim 4.

13. (New) Thin film formed of an Ag base alloy as set forth in Claim 5.

14. (New) Thin film formed of an Ag base alloy as set forth in Claim 6.

15. (New) Thin film formed of an Ag base alloy as set forth in Claim 7.

16. (New) Thin film formed of an Ag base alloy as set forth in Claim 8.